

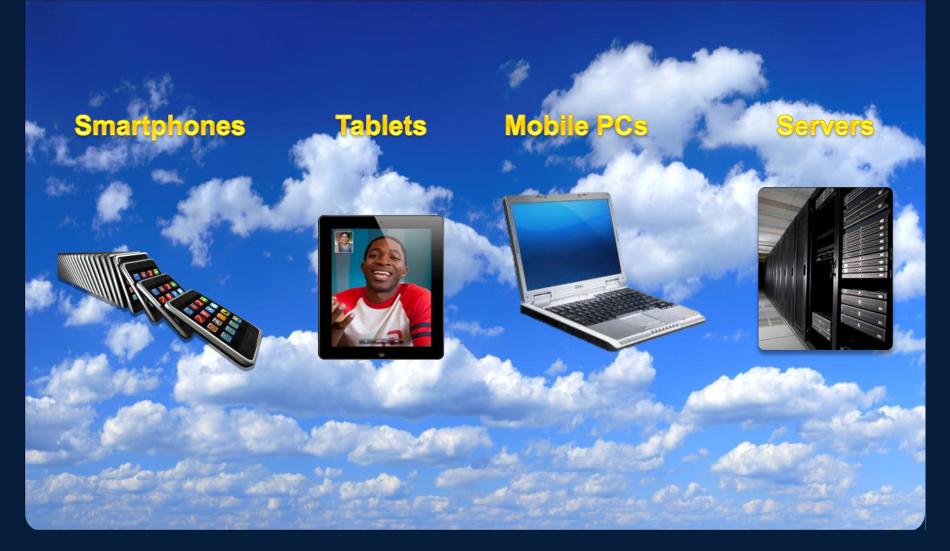
Applied Vantage Vulcan™ RTP

Optimizing Spike Anneals for 32nm and Beyond

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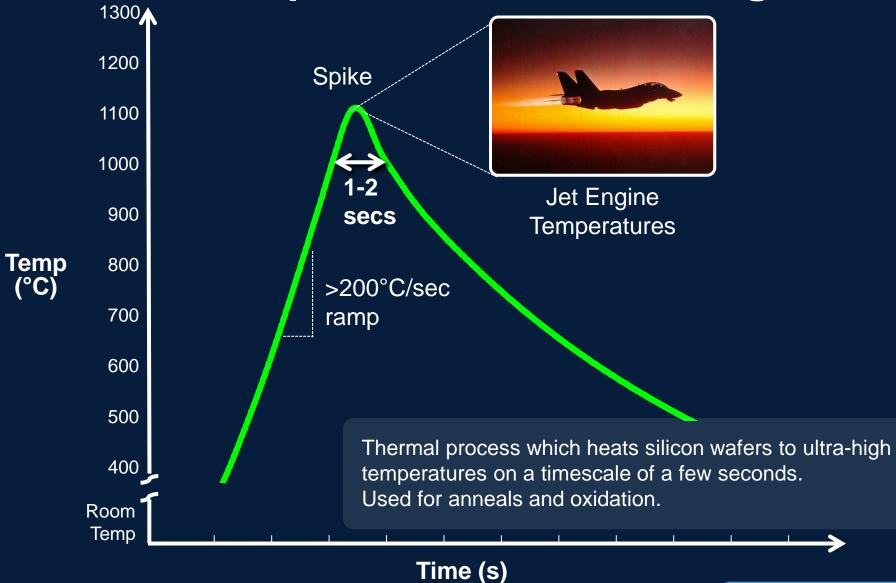
External Use



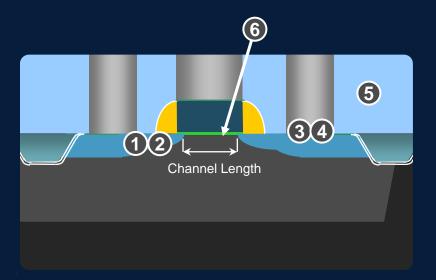
Mobility and Connectivity Driving Growth in Lower Power, High Performance Chips

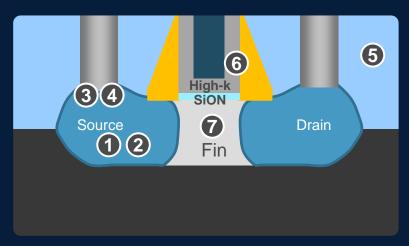


What is Rapid Thermal Processing?



Multiple RTP Steps in Advanced Transistors





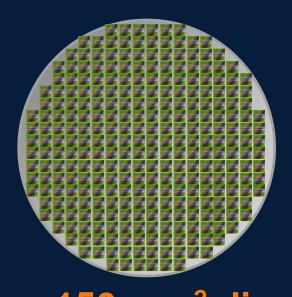
Advanced Planar Transistor

FinFET Transistor

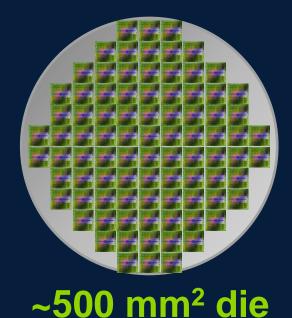
12	Source/Drain Anneals
34	Silicide Anneals
5	Inter-Layer Dielectric Anneal
6	High-k Densification Anneal
7	Fin Implant Anneal



Challenge #1: Bigger Die Increase the Within-Die Uniformity Challenge



~150 mm² die
130nm
technology node
graphics chip



40nm technology node graphics chip

Less Margin For Error

Source: NVIDIA



Challenge #2: Temperature Micro-Climates Add Within-Die Variation



Dense City

32°C



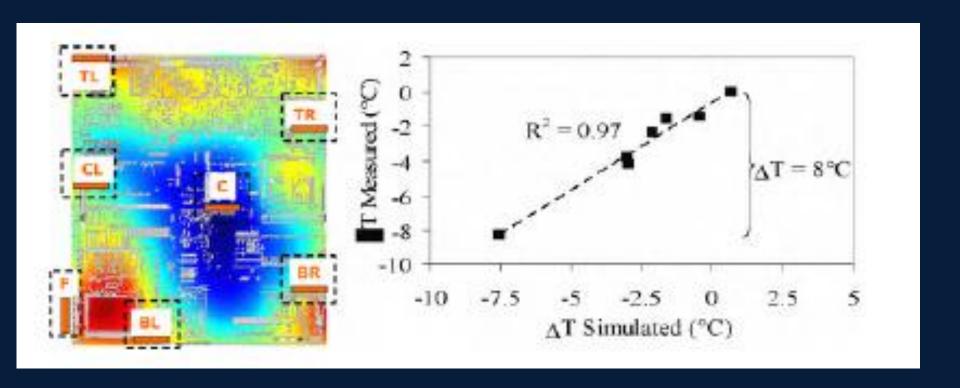
Open Field

25°C

Customers Currently Change Design Rules to Combat This Effect

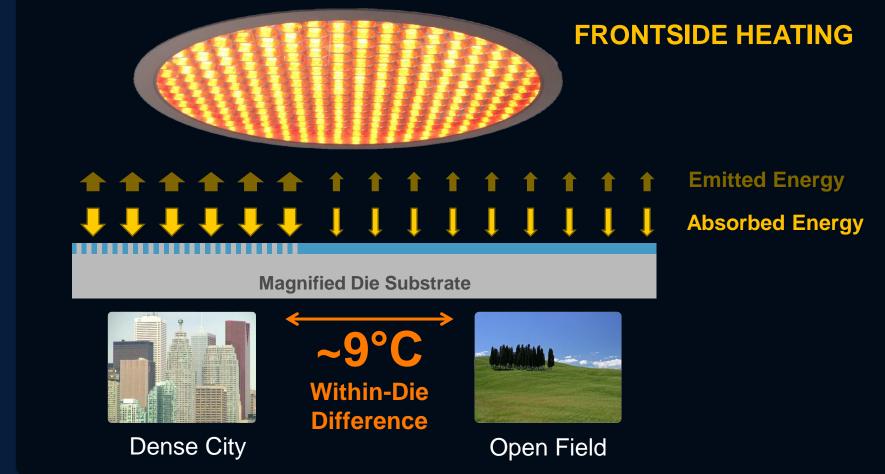


Production Data



Ring Oscillator test structures confirm temperature distribution based on design density





Within-Die Spike Anneal Thermal Variability With Frontside Heating





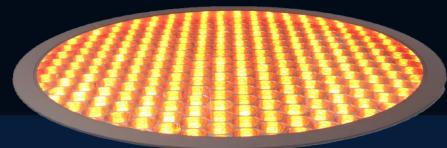
Dense City







Uniform
Absorbed
and Emitted
Energy

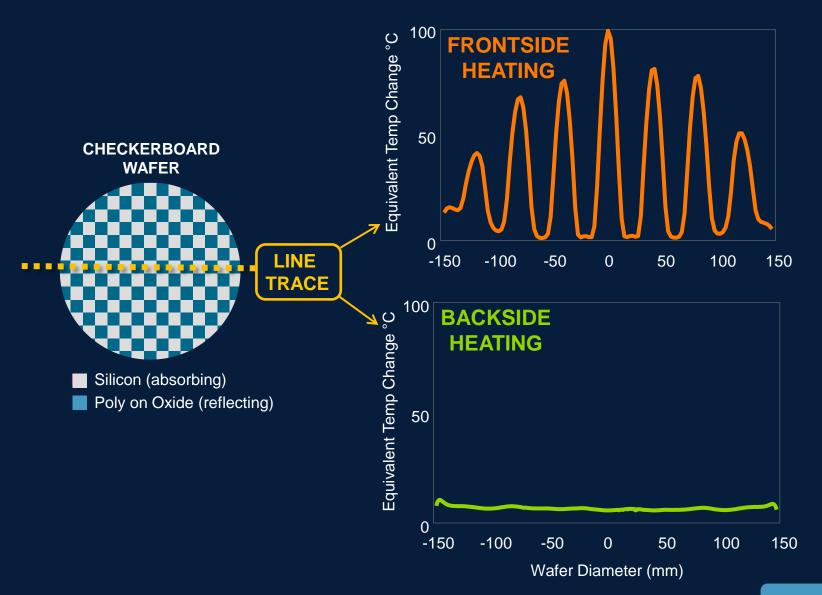


BACKSIDE HEATING

3X Decrease in Within-Die Thermal Variability With Vulcan System's Backside Heating

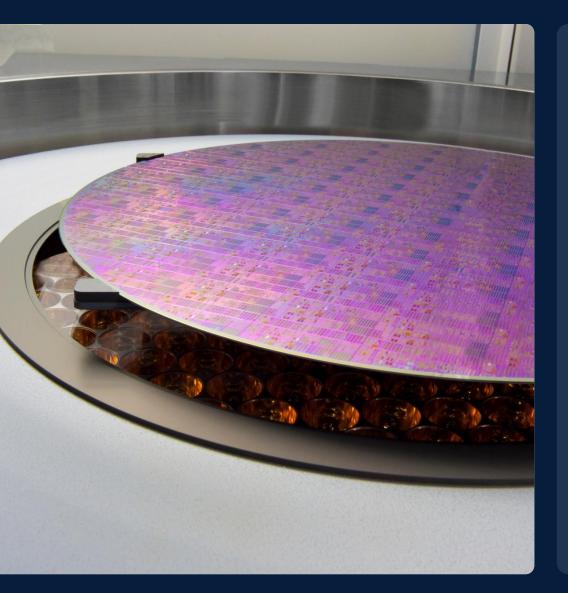


Extreme Test For Within-Die Uniformity





Introducing Applied Vantage Vulcan RTP



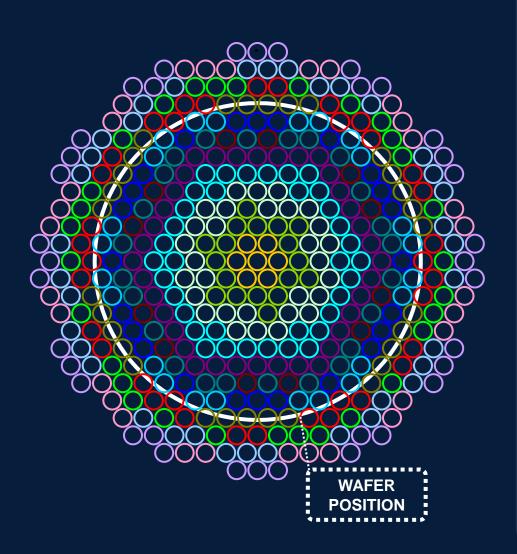
Revolutionary backside heating design

Extends Applied's technology leadership in ~\$500M market

Source: Gartner Dataquest April '11



Best-in-Class Dynamic Temperature Control



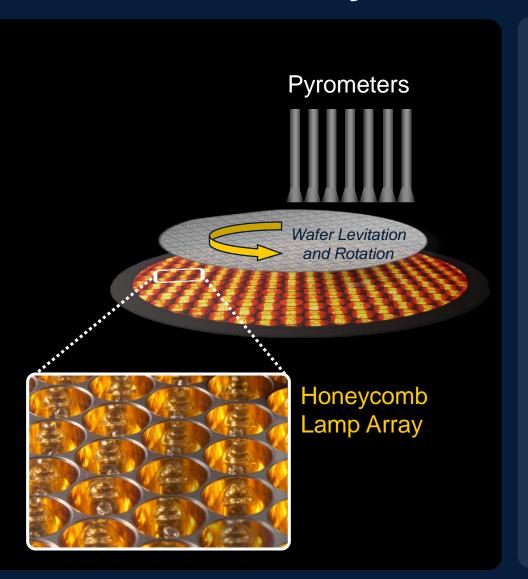
Proven honeycomb design with 18 zones

0.1% control of peak temperature

100 cycles-per-second multi-zone control



Best-in-Class Dynamic Temperature Control



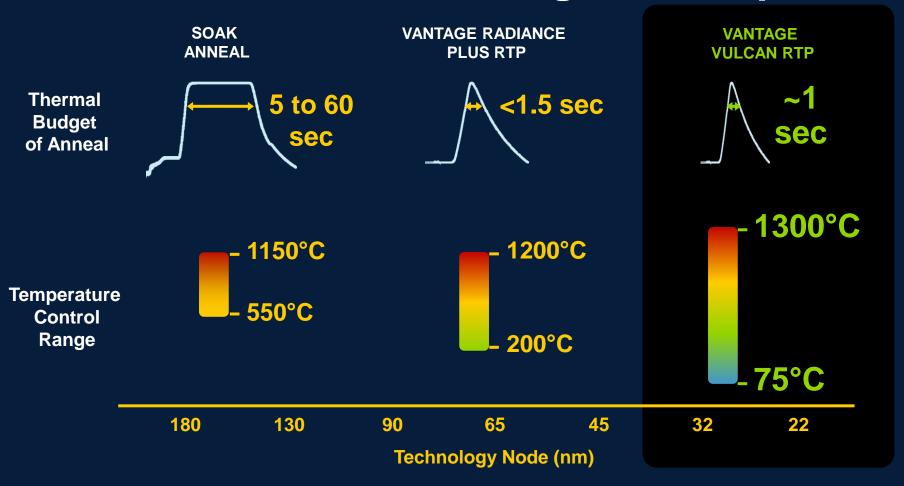
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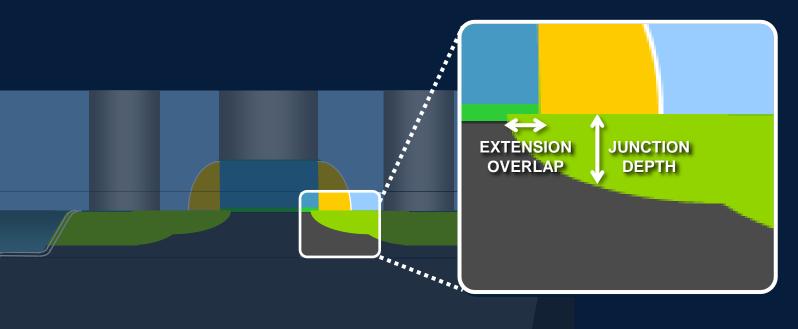
Thermal Processing Roadmap



Enabling 28nm Node and Beyond With Sharper Spikes and Full-Range Temperature Control

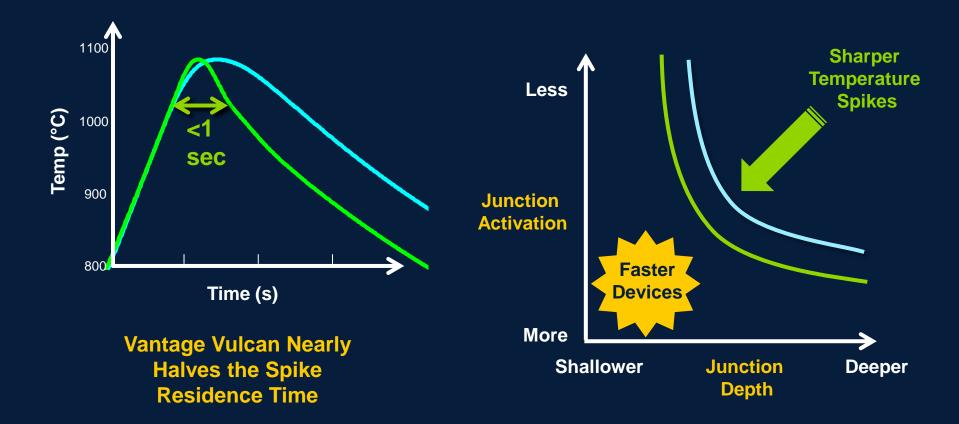


Atomic-Level Precision Required for Ultra-Shallow Junctions



Junction Diffusion Depth Must Be Reduced Without Compromising Activation

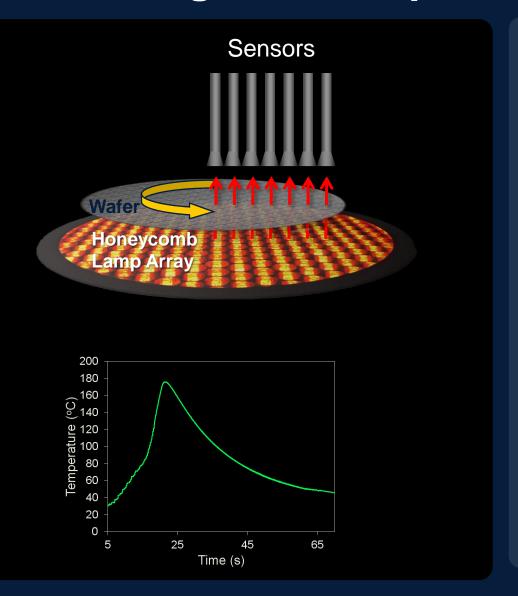




Faster Devices Through Sharper Temperature Ramp Profiles



Enabling Low-Temperature Regime Control



Closed-loop control from <75°C

Unique sensors for accurate, low-temperature measurement

New capability for advanced low-temperature applications



Industry's Greenest RTP Solution

CARBON FOOTPRINT REDUCTION*

= 4 CARS OFF THE ROAD

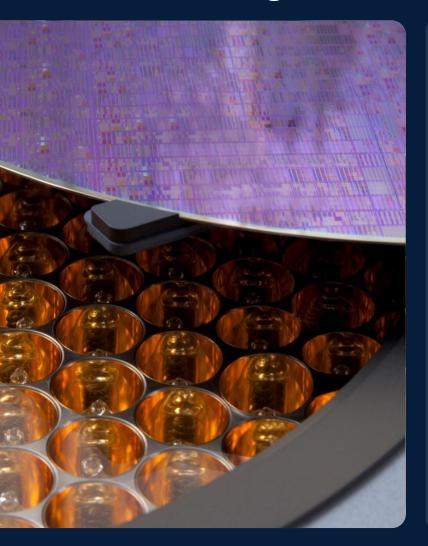


Advanced system design improves usage of grid energy



^{*} Per system; equivalent to 16 metric tons of CO₂/year

Applied Vantage Vulcan RTPContinuing RTP Leadership for the Next Decade



Best-in-class temperature uniformity for higher yield

Sharper temperature spikes for faster chips

Low-temperature control for new applications

Efficient energy usage for lower carbon footprint





Turning innovations into industries.™